



1. Title:	Selete Mask Handling Program
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3. Abstract body:

Selete started a new EUV program in April, 2006. Development of EUV mask handling technology is one of the key areas of the program. We plan to evaluate EUV mask carriers using Mask Protection Engineering Tool (MPE Tool) and a particle inspection tool with the defect sensitivity less than 50nm. MPE Tool can handle masks with protective enclosures which Canon and Nikon are proposing, and can be modified to handle another carrier as the need arises.

MPE Tool has a robot in the air, and it transfers a naked mask or a mask with a protective enclosure from RSP200 to the loadlock. A robot in vacuum transfers the mask from the loadlock onto the electro static chuck. MPE Tool has some reserved ports for various purposes. The inspection tool will be installed in Selete, Tsukuba, in July 2006, and MPE Tool will be in December 2006. We expect to report some results of carrier shipping tests at this symposium.

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